

ABSTRACT OF THE DISCLOSURE (FIG. 2)

"METHOD OF FORMING PATTERNS AND METHOD OF
MANUFACTURING MAGNETIC RECORDING MEDIA"

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According to one embodiment, a method of forming
patterns is provided, in which the method including
forming a resist on an underlying material, pressing a
stamper having patterns of protrusions and recesses,
10 sidewalls of which protrusions are tapered, onto the
resist to form a patterned resist having patterns of
protrusions and recesses, sidewalls of which
protrusions are tapered, forming a protective film on
the patterned resist, performing anisotropic etching
15 to leave the protective film on the tapered sidewalls
of protrusions of the patterned resist, etching a
resist residue remaining in recesses of the patterned
resist using the protective film as a mask, and
etching the underlying material using the protective
20 film and the patterned resist as a mask.



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